L Number	Hits	Search Text	DB	Time stamp
-	22	(("20020042029") or ("6040965") or ("5932396") or ("6480355") or ("5747198") or ("6289578") or ("5725997") or ("6483664") or ("6501618") or ("6504678") or ("20010010885") or ("20010019036") or ("20010027029") or ("6465149") or ("20010019465") or ("20010035355") or ("20010038517") or ("20010035343") or ("20020037476") or ("20020071211") or ("20030007295") or ("20020187430")).PN.	USPAT; US-PGPUB	2003/03/07 17:11
-	61373	((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/07 17:59
-	2793	(((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/07 18:00
-	2003	((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/07 19:27
-	65	(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/07 19:04

–	23	(((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill$3 or ion adj beam or FIB or RIE or ion adj etch$3 or sputter$3) or (lift adj off or liftoff or remov$3 or etchback or etch$3 adj back)) near5 (resist or photoresist or imag$3 or pattern$3))) and ((heat$3 or bak$3) with (resist or photoresist or imag$3 or pattern$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/07 19:03
–	56	(((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill$3 or ion adj beam or FIB or RIE or ion adj etch$3 or sputter$3) or (lift adj off or liftoff or remov$3 or etchback or etch$3 adj back)) near5 (resist or photoresist or imag$3 or pattern$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/07 19:02

| - | | 33 | ((((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))))) and (((mill$3 or ion adj beam or FIB or RIE or ion adj etch$3 or sputter$3) or (lift adj off or liftoff or remov$3 or etchback or etch$3 adj back)) near5 (resist or photoresist or imag$3 or pattern$3))) not ((((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))))) and (((mill$3 or ion adj beam or FIB or RIE or ion adj etch$3 or sputter$3) or (lift adj off or liftoff or remov$3 or etchback or etch$3 adj back)) near5 (resist or photoresist or imag$3 or pattern$3))) and ((heat$3 or bak$3) with (resist or photoresist or imag$3 or pattern$3))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/08 15:24 |

| | | 9 | (((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) not (((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill$3 or ion adj beam or FIB or RIE or ion adj etch$3 or sputter$3) or (lift adj off or liftoff or remov$3 or etchback or etch$3 adj back)) near5 (resist or photoresist or imag$3 or pattern$3))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/07 19:05 |

-	1938	(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/10 15:26
-	1	("5872693").PN.	USPAT; US-PGPUB	2003/03/08 15:24
-	2	(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))))) and (polymethylglutarimide)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/08 17:56

-	0	(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) not ((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto$15) or (GMR same magneto$15)).ti,ab.) and (resist or photoresist or photopolymer$7 or photoimag$5)) and ((ash$3 or (ash adj treat$4) or etch$3 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or trim$4 or less$5 or tight$4) same (resist or photoresist or imag$3 or pattern$3))) and ((resist or photoresist or imag$3 or pattern$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))))) and (napthoquinonediazide or napthoquinonediazido)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/08 18:00
-	51	(resist or photoresist) and (napthoquinonediazide or napthoquinonediazido)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/08 18:22
-	3	((resist or photoresist) and (napthoquinonediazide or napthoquinonediazido)) and (novolac or novolak) and dissolution near3 accelerat$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/08 18:24
-	5	("4524121" | "4745042" | "5252831" | "5604073" | "5800963").PN.	USPAT	2003/03/10 09:27
-	45	(430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash$3 or etch$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/10 15:51
-	25	((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash$3 or etch$3))) and (heat$3 or bak$3) same (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/10 17:36
-	216	430/328.ccls. and (heat$3 or bak$3) same (expos$3) same (develop$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/10 17:38
-	211	(430/328.ccls. and (heat$3 or bak$3) same (expos$3) same (develop$3)) not (((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash$3 or etch$3))) and (heat$3 or bak$3) same (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/10 17:39